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Impact of Technostress on Job Satisfaction and Organizational Commitment

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Wei Qiu

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Abstract

Due to the fast development of ICT technology, both our private and professional lives have changed fundamentally. By using mobile computing communication devices and computer networks, people have the ability to access information quickly; real-time information sharing with colleagues that can happen anytime and anywhere. Thus employees may feel forced to be always connected and respond to work-related issues at any time, and so lose the control of their personal lives. With the adoption of ICTs, organizations are taking on the pressures of frequent re-engineering and process changes, driven by the ICT changes and upgrades. Although the evolution of ICTs has brought numerous potential benefits to the organization, employees often feel frustrated and distressed when they are not able to cope with the demands of organizational computer usage. Recent literature has named this technology-related stress “technostress”.

The primary objective of the present study is to develop and validate a model that analyzes the effects of factors that create technostress, and examines its relationship with job satisfaction and organizational commitment. In addition, this study also attempts to identify a mechanism that can potentially alleviate the negative effects of technostress. It examines how user involvement as a technostress inhibitor affects technostress, job satisfaction and organizational outcomes.

The result is based on a survey data analysis of 215 people who work in New Zealand . A structural equation modeling technique was applied to examine the simultaneous casual relationships between technostress creators and other variables, and further, to explain them Results from the present study found that technostress is a significant factor in predicting employee job satisfaction, which in turn impacts on their organizational commitment. It also provides evidence for the mediating effect of job satisfaction in the relationship between stress and organizational commitment. In addition, this study highlights the complex nature of user involvement and its complex relationship with other organizational and individual factors.

The technology world will continue to advance; organizations will continually introduce new technology to keep up with competition in the market, and employees cannot avoid continually increasing their daily interactions with ICTs. This study demonstrates potential negative effects of technostress for ICT usage in organizations. The results of the study suggest that technostress is an important factor in predicting the job satisfaction of employees, which in turn influences their commitment to the organization.

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